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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Kazuhide HASEBE, et al.

International Application No.: PCT/JP2004/005643

International Filing Date: April 20, 2004

U.S. Serial No.: To Be Assigned

Group Art Unit: To Be Assigned

Filed: : Herewith

Examiner: To Be Assigned

For: SILICON DIOXIDE FILM REMOVING METHOD AND  
PROCESSING SYSTEM

PRELIMINARY AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Prior to or concurrent with calculation of the filing fees, please amend this  
application as follows.